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- ☒ Classification codes B: Electrical & Electronics, 0-5

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 PALM INTRANET

## Inventor Information for 09/995421

Inventor Name	City	State/Country
CHUNG, WON-YOUNG	KYUNGKI-DO	KOREA, REPUBLIC OF
KIM, TAI-KYUNG	KYUNGKI-DO	KOREA, REPUBLIC OF
OH, JAE-JOON	SUNGNAM-CITY	KOREA, REPUBLIC OF

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## Inventor Name Search Result

Your Search was:

Last Name = CHUNG

First Name = WON-YOUNG

Application#	Patent#	Status	Date Filed	Title	Inventor Name 6
<u>11028202</u>	Not Issued	020	01/04/2005	PHASE-CHANGE MEMORY DEVICE AND METHOD OF MANUFACTURING THE SAME	CHUNG, WON-YOUNG
<u>11017594</u>	Not Issued	030	12/20/2004	PHASE CHANGE MEMORY DEVICES INCLUDING MEMORY ELEMENTS HAVING VARIABLE CROSS-SECTIONAL AREAS	CHUNG, WON-YOUNG
<u>10983023</u>	Not Issued	041	11/05/2004	METHOD AND APPARATUS FOR DRYING A WAFER, AND AN APPARATUS FOR CLEANING AND DRYING A WAFER	CHUNG, WON-YOUNG
<u>10956567</u>	Not Issued	030	10/01/2004	COLOR-CONVERTING LIGHT EMITTING DEVICE INCLUDING FLUORESCENT POWDER HAVING LARGE GRAIN DIAMETER, METHOD OF PRODUCING THE SAME, AND RESIN COMPOSITION USED THEREIN	CHUNG, WON-YOUNG
<u>09995421</u>	Not Issued	030	11/27/2001	METHODS, APPARATUS AND COMPUTER PROGRAM PRODUCTS FOR SIMULATING PLASMA BEHAVIOR IN A PLASMA REACTOR APPARATUS USING TWO-DIMENSIONAL CROSS-SECTION COMPUTATIONS	CHUNG, WON-YOUNG
<u>07739165</u>	<u>5116223</u>	150	08/01/1991	SWING ARM FOR SUPPORT OF DENTIST'S SUCTION PUMP NOZZLE	CHUNG, WON-YOUNG

Inventor Search Completed: No Records to Display.

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## PALM INTRANET

### Inventor Name Search Result

Your Search was:

Last Name = KIM

First Name = TAI-KYUNG

Application#	Patent#	Status	Date Filed	Title	Inventor Name 3
<u>11028202</u>	Not Issued	020	01/04/2005	PHASE-CHANGE MEMORY DEVICE AND METHOD OF MANUFACTURING THE SAME	KIM, TAI-KYUNG
<u>11017594</u>	Not Issued	030	12/20/2004	PHASE CHANGE MEMORY DEVICES INCLUDING MEMORY ELEMENTS HAVING VARIABLE CROSS-SECTIONAL AREAS	KIM, TAI-KYUNG
<u>09995421</u>	Not Issued	030	11/27/2001	METHODS, APPARATUS AND COMPUTER PROGRAM PRODUCTS FOR SIMULATING PLASMA BEHAVIOR IN A PLASMA REACTOR APPARATUS USING TWO-DIMENSIONAL CROSS-SECTION COMPUTATIONS	KIM, TAI-KYUNG

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**Inventor Name Search Result**


Your Search was:

Last Name = OH

First Name = JAE-JOON

Application#	Patent#	Status	Date Filed	Title	Inventor Name 6
<u>11007878</u>	Not Issued	020	12/09/2004	ELECTRON CYCLOTRON RESONANCE EQUIPMENT WITH VARIABLE FLARE ANGLE OF HORN ANTENNA	OH, JAE-JOON
<u>10969928</u>	Not Issued	030	10/22/2004	ANTENNA FOR USE IN PRODUCING PLASMA AND PLASMA PROCESSING APPARATUS COMPRISING THE SAME	OH, JAE-JOON
<u>10909467</u>	Not Issued	030	08/02/2004	APPARATUS FOR GENERATING INDUCTIVELY-COUPLED PLASMA AND ANTENNA COIL STRUCTURE THEREOF FOR GENERATING INDUCTIVE ELECTRIC FIELDS	OH, JAE-JOON
<u>10844804</u>	Not Issued	020	05/13/2004	ELEMENTARY PLASMA SOURCE AND PLASMA GENERATION APPARATUS USING THE SAME	OH, JAE-JOON
<u>10449777</u>	<u>6806437</u>	150	06/02/2003	INDUCTIVELY COUPLED PLASMA GENERATING APPARATUS INCORPORATING DOUBLE-LAYERED COIL ANTENNA	OH, JAE-JOON
<u>09995421</u>	Not Issued	030	11/27/2001	METHODS, APPARATUS AND COMPUTER PROGRAM PRODUCTS FOR SIMULATING PLASMA BEHAVIOR IN A PLASMA REACTOR APPARATUS USING TWO-DIMENSIONAL CROSS-SECTION COMPUTATIONS	OH, JAE-JOON

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### [Department of Chemical Engineering](#)

BN Ramamurthi and DJ Economou, "**Two-Dimensional** Simulation of Pulsed-Power ...

DJ Economou, "Modeling and Simulation of **Plasma Etching** Reactors for ...

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### [Etching of Polysilicon in an Inductively Coupled Reactor:](#)

Tait et al. modified a **2-dimensional plasma etching** model based on the ...

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### [NIST Reacting Flows Group Showcase \(24\)](#)

of CF<sub>2</sub> in a Parallel Plate **Plasma Etching Reactor** ... "**Two-Dimensional** Argon

Metastable Density Measurements in a Radio Frequency **Plasma Reactor** by Planar ...

[www.nist.gov/cstl/div836/836.03/show24.html](http://www.nist.gov/cstl/div836/836.03/show24.html) - 5k - [Cached](#) - [Similar pages](#)

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in a Parallel Plate **Plasma Etching Reactor** (click on image to enlarge) ...

BK McMillin and MR Zachariah, "**Two-Dimensional** Argon Metastable Density ...

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A **two dimensional** wave propagation code, developed specifically to simulate ...

[GP1.130] Atomic-scale study on **plasma etching** using classical molecular ...

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The **two-dimensional plasma** modeling code PLASMATOR™ marketed by Kinema Research

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